

<b>INFORMATION DISCLOSURE CITATION</b> <small>(Use several sheets if necessary)</small>				ATTY DOCKET NO. 2004US301	APPLICATION NO. 10/808,884		
				APPLICANT(S) Yu SUI et al.			
				FILING DATE March 25, 2004	GROUP ART UNIT 1756		
<b>U.S. PATENT DOCUMENTS</b>							
*EXAMINER INITIAL	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE	
<i>WY</i>	6,319,651 B1	11/20/2001	Holmes et al.	430	270.1		
	4,491,628	01/01/1985	Ito et al.	430	176		
	5,350,660	09/27/1994	Urano et al.	430	176		
<i>WY</i>	4,863,827	09/05/1989	Jain et al.	430	145		
<i>WY</i>	5,939,236	08/17/1999	Pavelchek et al.	430	273.1		
<b>U.S. PATENT APPLICATION PUBLICATIONS</b>							
*EXAMINER INITIAL	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE	
<i>WY</i>	2004/0018451 A1	01/29/2004	Choi	430	313		
<b>FOREIGN PATENT DOCUMENTS</b>							
	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION	
						YES	NO
<i>WY</i>	EP 0 794 458 A2	09/10/1997	EUROPE				
	GB 2 320 718 A	07/01/1998	GREAT BRITAIN				
	DE 30 30 086 A1	03/21/1991	GERMANY				
	DE 39 30 087 A1	03/14/1991	GERMANY				
	DE 41 12 967 A1	10/22/1992	GERMANY				
<b>OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)</b>							
<i>WY</i>		Yamaoka et al., "Photochemical Dissociation of p-Nitrobenzyl Aromatic Sulfonate and Its Application to Chemical Amplification Resists", <i>Journal of Photopolymer Science and Technology</i> , Vol. 3, No. 3 (1990), pp. 275 - pp. 280					
<i>WY</i>		Schlegel et al., "Studies on the Acid Formation and Deprotection Reaction by Novel Sulfonates in a Chemical Amplification Positive Photoresist", <i>Journal of Photopolymer &amp; Science Technology</i> , Vol. 3, No. 3 (1990), pp. 281 - pp. 287					
EXAMINER <i>WY</i>				DATE CONSIDERED		<i>8/23/05</i>	
<small>*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.</small>							

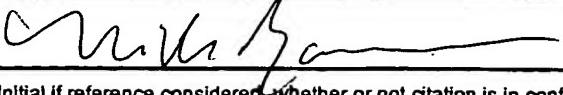
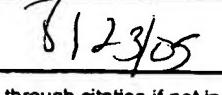
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*EXAMINER INITIAL	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
<i>nm</i>	5,886,102	03/23/1999	Sinta et al.	<i>525</i>	<i>154</i>	
<i>l</i>	6,110,653	08/29/2000	Holmes et al.	<i>430</i>	<i>325</i>	
<i>l</i>	6,080,530	06/27/2000	Shao et al.	<i>430</i>	<i>325</i>	
<i>df</i>	6,251,562 B1	06/26/2001	Breyta et al.	<i>430</i>	<i>287.1</i>	
<i>nm</i>	4,910,122	3/20/1990	Arnold et al.	<i>430</i>	<i>313</i>	
U.S. PATENT APPLICATION PUBLICATIONS						
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						YES
<i>nm</i>	WO 97/33198	09/12/1997	WIPO			
OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)						
<i>nm</i>		Shirai et al., "Photochemistry of Imino Sulfonate Compounds and Their Application to Chemically Amplified Resists", <i>Journal of Photopolymer Science and Technology</i> , Vol. 3, No. 3 (1990), pp. 301 - pp. 304				
<i>nm</i>		CRC Handbook of Chemistry & Physics, "Dissociation Constants Of Organic Acids And Bases", CRC Press (1994-1995 75th Edition), pp. 8-45 - pp. 8-55				
EXAMINER	<i>Milena G.</i>		DATE CONSIDERED		<i>3/23/05</i>	
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nm	5,635,333	06/03/1997	Petersen et al.	430	311	
	5,882,996	06/16/1999	Dai	438	697	
	6,319,651 B1	11/20/2001	Holmes, et al.	430	270.1	
ex	6,054,254	04/25/2000	Sato et al.	430	322	
WJ	6,114,085	09/05/2000	Padmanaban et al.	430	270.1	
U.S. PATENT APPLICATION PUBLICATIONS						
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						YES
						NO
OTHER DOCUMENTS <i>(Including Author, Title, Date, Pertinent Pages, Etc.)</i>						
WJ		Moon et al., "Three-Component Photopolymers Based on Thermal Cross-Linking and Acidolytic De-Cross-Linking of Vinyl Ether Groups. Effects of Binder Polymers on Photopolymer Characteristics, <i>Chemical Materials</i> , Vol. 6 (1994), pp. 1854 - pp. 1860				
WJ		Abstract of Houlihan et al., "Chemically amplified resists. The chemistry and lithographic characteristics of nitrobenzyl benzenesulfonate derivatives", <i>Journal of Photopolymer &amp; Science Technology</i> , Vol. 3, pp. 259 - pp. 273 (1990)				
EXAMINER <i>Wendy J. Munoz</i>			DATE CONSIDERED 8/23/05			
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Wm		5,652,297	07/29/1997	McCulloch et al.	524	555	
		5,981,145	11/09/1999	Ding et al.	430	271.1	
		6,187,506 B1	02/13/2004	Ding et al.	430	271.1	
Wm		5,939,236	08/17/1999	Pavelchek et al.	430	273.1	
Wm		5,935,760	08/10/1999	Shao et al.	430	271.1	
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OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)							
Wm		Abstract of Yamaoka et al., "Reactions of vinyl ethers and application to photoreactive process", Trends in Photochemistry & Photobiology, Vol. 7, pp. 45 - pp. 70 (2001)					
Wm		Abstract of Schacht et al., "Acid labile crosslinked units: a concept for improved positive deep-UV photoresists", ACS Symposium Series, 706, pp. 78 - pp. 94 (1998)					
EXAMINER		<i>Mark M</i>		DATE CONSIDERED		<i>7/23/05</i>	
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<i>nmj</i>		5,731,386	03/24/1998	Thackeray et al.	525	327.2	
<i>j</i>		5,880,169	03/09/1999	Osawa et al.	522	25	
		5,354,643	10/11/1994	Cabrera et al.	4130	270.1	
<i>of</i>		5,716,756	02/10/1998	Pawlowski et al.	4130	270.1	
<i>Wm</i>		5,069,997	12/03/1991	Schwalm et al.	4130	270.1	
<b>U.S. PATENT APPLICATION PUBLICATIONS</b>							
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EXAMINER <i>Mary Bannister</i>			DATE CONSIDERED <i>8/23/05</i>				

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RM	5,585,219	12/17/1996	Kaimoto et al.		4130	270.1	
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